H2 prior at a Ford 2/18/99

Inventor:

Klaus F. Schuegraf

Title:

Semiconductor Processing Methods of Chemical Vapor

Depositing SiO<sub>2</sub> on a Substrate

Assignee:

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Micron Technology, Inc.

## **INFORMATION DISCLOSURE STATEMENT**

References -- See Attached Form PTO-1449

The attached form PTO-1449 is submitted in compliance with 37 CFR §1.56. No admission is made regarding whether all the submitted references are prior art.

Respectfully submitted,

Dated: 1/15/18

Attorney:

Lance R. Sadler

Reg. No.: 38,605

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